

LGAD sensor status

MEI ZHAO

2025-12-05

Contract

- CERN procurement part: 54% of total sensors[585+11723]
- IME and CERN contract be signed at beginning of 2025.

INSTITUTE OF MICROELECTRONICS OF
CHINESE ACADEMY OF SCIENCES
 Name: Xiaohai Wang
 Title: Director of Integrated Circuit Advanced
Process R&D Center of IMECAS
 Signature: *Xiaohai Wang*
 Date:

EUROPEAN ORGANISATION FOR NUCLEAR
RESEARCH
 Name: Cristina Lara
 Title: Head of Procurement
 Signature: *CLA*
 Date: 06 February 2025

BEIJING QIU SHI HIGH ENERGY TECH-
DEVELOPING COMPANY
 Name: *Zhao Jianming*
 Title: Legal Representative
 Signature:

Name: Christopher Hartley
 Title: Head of IPT Department
 Signature: *[Signature]*
 Date: 06 February 2025

CERN
 ORGANISATION EUROPEENNE POUR LA RECHERCHE
NUCLEAIRE

| | Milestones | Latest delivery date |
|----|--|----------------------|
| T0 | Notification of the award of the Contract to IME (Letter of Intent already released) | Done |
| | Delivery of Detailed Design File and Quality Plan (already received) | Done |
| T1 | Acceptance by CERN of the abovementioned documentation | Done |
| | Delivery of Pre-Series at CERN and associated documentation (see § 5.1 of the Technical Specification – Annex I) | Done |
| T2 | Authorisation by CERN to manufacture the Series on the basis of Pre-Series acceptance | 30 January 2025 |
| | Delivery of pilot batch (batch no. 0) of Series units at CERN and associated documentation (see § 5.1 of the Technical Specification – Annex I) | 30 April 2025 |
| | Delivery of first batch (batch no. 1) of Series units at CERN and associated documentation (see § 5.1 of the Technical Specification – Annex I) | 30 July 2025 |
| | Delivery of second batch (batch no. 2) of Series units at CERN and associated documentation (see § 5.1 of the Technical Specification – Annex I) | 30 October 2025 |
| | Delivery of third batch (batch no. 3) of Series units at CERN (70% of the total Supply) and associated documentation (see § 5.1 of the Technical Specification – Annex I) | 30 January 2026 |
| | Delivery of fourth batch (batch no. 4) of Series units at CERN and associated documentation (see § 5.1 of the Technical Specification – Annex I) | 30 April 2026 |
| | Delivery of fifth batch (batch no. 5) of Series units (last batch of Production units) at CERN and associated documentation (see § 5.1 of the Technical Specification – Annex I) | 30 July 2026 |

Delivery timeline

Contract signed

Pilot batch: done

First batch

Second batch

Third batch

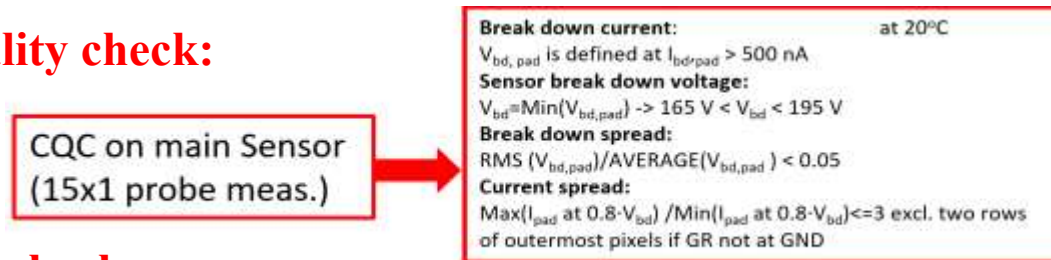
Fourth batch

Fifth batch

Acceptance criteria for LGAD sensors

➤ Wafers and sensors passing the following qualification tests will be accepted

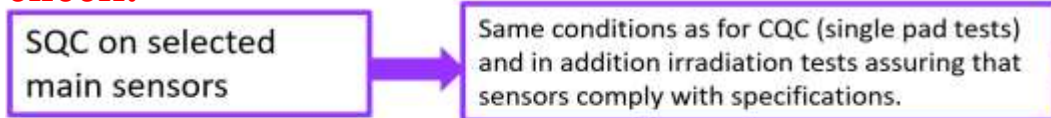
Company quality check: CQC



Sensor passed CQC?

YES

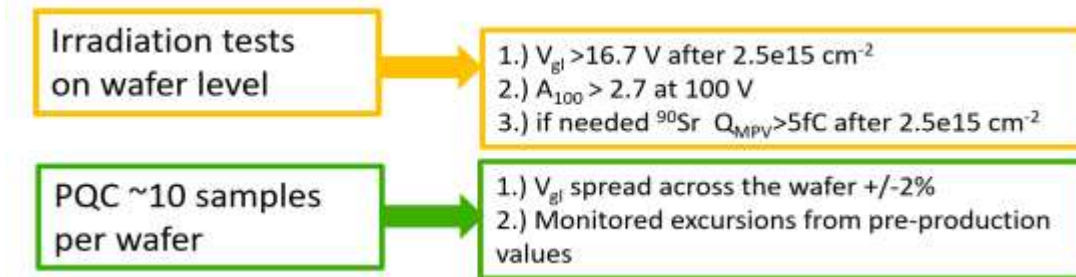
Sensor quality check: SQC



Sensors passed SQC?

YES

Sensor irradiation test: IT



Wafer passed IT?

YES

Wafer passed PQC?

YES

SENSOR ACCEPTED

Sensor tests

Wafer tests

Acceptance criteria for LGAD sensors

➤ Main sensors be separated as 3 classes: A, B1 and B2, C.

➤ **A**: sensor passes all the acceptance criteria.

Break down current:

$I_{bd,15\text{ pad}} = 15 \cdot I_{\text{pad,bd}} \rightarrow V_{bd,15\text{ pad}}$ is defined at $I_{15\text{ pad}} > 7500\text{ nA}$, where $I_{\text{pad,bd}}$ is the pad current breakdown threshold.

- **Sensor break down voltage:**

$V_{bd} = \text{Min}(V_{bd,15\text{ pad}}) \rightarrow 165\text{V} < V_{bd} < 195\text{V}$

- **Break down spread:**

$\text{RMS}(V_{bd,15\text{ pad}})/\text{AVERAGE}(V_{bd,15\text{ pad}}) < 0.05$

- **Current spread:**

$\text{Max}(I_{15\text{ pad}} \text{ at } 0.8 \cdot V_{bd})/\text{Min}(I_{15\text{ pad}} \text{ at } 0.8 \cdot V_{bd}) \leq 2.5$

at 20°C

Lower V_{bd}

➤ **B1**: sensor with $150\text{V} < V_{bd} < 165\text{V}$, fills the leakage current requirement

Larger leakage current ratio

➤ **B2**: sensor fill Current spread criteria with

$2.5 < \text{Max}(I_{15\text{ pad}} \text{ at } 0.8 \cdot V_{bd})/\text{Min}(I_{15\text{ pad}} \text{ at } 0.8 \cdot V_{bd}) < 10.$

CERN will accept the sensors if they are of category A.

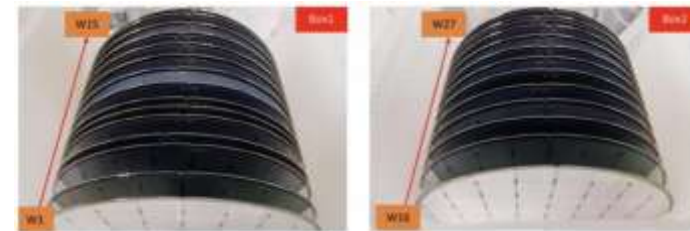
CERN reserves the right to review and possibly accept sensors of quality B if the need emerges.

Production status: next batches

| Batch | Required sensor number | Delivered time on contract | Status |
|-----------------------|------------------------|----------------------------|---|
| Pre-production | 586 | | Accepted by HGTD group, and be delivered to hybridization sites. |
| Pilot batch | 400 | 30 April 2025 | 403 sensors has been delivered to IHEP |
| 1 st batch | 2736 | 30 July 2025 | ~2700 sensors. First 50 wafers been packaged, QC-TS be delivered to IHEP. Next 50 wafers under picking, will be delivered by 15 Dec. 2025 |
| 2 nd barch | 2736 | 30 October 2025 | 2376 sensors[100 wafers] have completed UBM and dicing, will be ready to delivery by 30 Jan. 2026 . [three months delay] |
| 3 rd batch | 2736 | 30 January 2026 | 2736 sensors[100 wafers] are under UBM in NCAP and will be ready to shipped on 30 Mar. 2026 |
| 4 th batch | 1757 | 30 April 2026 | Sensors are manufactured in IME, will be will be ready to shipped on 30 Apr. 2026 |
| 5 th batch | 1757 | 30 July2026 | Plan to be shipped on 30 July 2026 |

Pre-production sensor status

| ATLAS ID | IHEP-IME ID | thickness(um) | Average Vbd (V) | # of good sensors | sensor yield | UBM |
|----------------|-------------|---------------|-----------------|-------------------|--------------|-----|
| 20WS0000110002 | v1-R2(w1) | 775 | 212.7 | 19 | 37% | no |
| 20WS0000110003 | v1-R3(w2) | 775 | 222.5 | 25 | 48% | no |
| 20WS0000110016 | v1-A16(w3) | 775 | 196 | 18 | 35% | no |
| 20WS0000200012 | v2-12(w4) | 775 | 180.8 | 39 | 75% | no |
| 20WS0000110015 | v1A15 | 775 | 217.7 | 22 | 48% | yes |
| 20WS0000110005 | v1R5 | 300 | 190 | 42 | 80.77% | yes |
| 20WS0000200016 | v216 | 300 | 201.7 | 40 | 76.92% | yes |
| 20WS0000300010 | V310 | 300 | 196.1 | 31 | 59.62% | yes |
| 20WS0000400007 | V4-7 | 300 | 169.9 | 31 | 59.62% | yes |
| 20WS0000400009 | V4-9 | 300 | 168.2 | 33 | 63.46% | yes |
| 20WS0000400011 | V4-11 | 300 | 170.8 | 39 | 75.00% | yes |
| 20WS0000400012 | V4-12 | 300 | 170.7 | 33 | 63.46% | yes |
| 20WS0000400014 | V4-14 | 300 | 162.1 | 30 | 57.69% | yes |
| 20WS0000400015 | V4-15 | 300 | 172 | 39 | 75.00% | yes |
| 20WS0000400020 | V4-20 | 300 | 177.8 | 28 | 53.85% | yes |
| 20WS0000400022 | V4-22 | 300 | 160 | 26 | 50.00% | yes |
| 20WS0000400024 | V4-24 | 300 | 178.1 | 31 | 59.62% | yes |
| 20WS0000400001 | V4-1 | 300 | 178.1 | 43 | 82.69% | yes |
| 20WS0000400003 | V4-3 | 300 | 167.4 | 6 | 11.54% | yes |
| 20WS0000400013 | V4-13 | 300 | 174.9 | 40 | 76.92% | yes |
| 20WS0000400023 | V4-23 | 300 | 164.8 | 34 | 65.38% | yes |
| 20WS0000300001 | V3-1 | 300 | 178.1 | 43 | 82.69% | yes |
| 20WS0000300005 | V3-5 | 300 | 172.3 | 36 | 69.23% | yes |
| 20WS0000300015 | V3-15 | 300 | 177.6 | 38 | 73.08% | yes |
| 20WS0000300022 | V3-22 | 300 | 176.6 | 44 | 84.62% | yes |
| 20WS0000300023 | V3-23 | 300 | 171.1 | 39 | 75.00% | yes |
| 20WS0000300024 | V3-24 | 300 | 174.3 | 41 | 78.85% | yes |



| Production version | Wafer No. | Implantation | LGADs | VBD/mm | Labelled | Thinned | Backside (Al) | UBMol | Donor | Yield | Quality |
|-------------------------|-----------|--------------|-------|-----------|----------|---------|---------------|-------|-------|--------------|---------|
| USTC-IME Pre-production | W1 | B+1C | 15x15 | ~ 182.8 V | Done | | | | | 17/52 ~ 33 % | |
| | W2 | B+1C | 15x15 | ~ 186.5 V | Done | Done | Done | | Done | 2/52 ~ 4 % | |
| | W3 | B+1C | 15x15 | ~ 193.7 V | Done | Done | Done | Ready | | 26/52 ~ 50 % | Good |
| | W4 | B+1C | 15x15 | ~ 199.8 V | Done | Done | Done | Ready | | 24/52 ~ 46 % | Good |
| | W5 | B+1C | 15x15 | ~ 191.7 V | Done | Done | Done | Ready | | 24/52 ~ 46 % | Good |
| | W6 | B+1C | 15x15 | ~ 188.5 V | Done | Done | Done | Ready | | 22/52 ~ 42 % | Good |
| | W7 | B+1C | 15x15 | ~ 184.9 V | Done | Done | Done | Ready | | 22/52 ~ 42 % | Good |
| | W8 | B+1C | 15x15 | ~ 186.2 V | Done | Done | Done | Ready | | 22/52 ~ 42 % | Good |
| | W9 | B+1C | 15x15 | ~ 195.6 V | Done | | | | | 13/52 ~ 25 % | |
| | W10 | B+1C | 15x15 | ~ 193.6 V | Done | | | | | 16/52 ~ 31 % | |
| | W11 | B+1C | 15x15 | ~ 192.3 V | Done | Done | Done | Ready | | 26/52 ~ 50 % | Good |
| | W12 | B+1C | 15x15 | ~ 193.1 V | Done | Done | Done | | Done | 13/52 ~ 25 % | |
| | W13 | B+1C | 15x15 | ~ 188.8 V | Done | Done | Done | Ready | | 21/52 ~ 40 % | Good |
| | W14 | B+1C | 15x15 | ~ 191.6 V | Done | Done | Done | Ready | | 18/52 ~ 35 % | Good |
| | W15 | B+1C | 15x15 | ~ 193.0 V | Done | | | | | 12/52 ~ 23 % | |
| | W16 | B+1C | 15x15 | ~ 152.4 V | Done | | | | | 23/52 ~ 44 % | |
| | W17 | B+1C | 15x15 | ~ 150.4 V | Done | | | | | 27/52 ~ 52 % | |
| | W18 | B+1C | 15x15 | ~ 137.7 V | Done | | | | | 25/52 ~ 48 % | |
| | W19 | B+1C | 15x15 | ~ 146.5 V | Done | | | | | 26/52 ~ 50 % | |
| | W20 | B+1C | 15x15 | ~ 138.9 V | Done | | | | | 20/52 ~ 38 % | |
| | W21 | B+1C | 15x15 | ~ 127.5 V | Done | | | | | 18/52 ~ 35 % | |
| | W22 | B+1C | 15x15 | ~ 143.6 V | Done | | | | | 21/52 ~ 40 % | |
| | W23 | B+1C | 15x15 | ~ 130.6 V | Done | | | | | 15/52 ~ 29 % | |
| | W24 | B+1C | 15x15 | ~ 151.8 V | Done | Done | Done | | Done | 21/52 ~ 40 % | |
| | W25 | B+1.3C | 15x15 | ~ 116.9 V | Done | Done | Done | | Done | 10/52 ~ 19 % | |
| | W26 | B+1.5C | 15x15 | ~ 111.8 V | Done | Done | Done | | Done | 13/52 ~ 25 % | |
| | W27 | B+0.7C | 15x15 | ~ 158.1 V | Done | Done | Done | | Done | 25/52 ~ 48 % | |

USTC-IME 27 wafers fabricated:
9 wafers core preproduction – all finished in accordance with specs and requirements

IHEP-IME: 90 wafers fabricated.
22 wafers: core preproduction – all finished in accordance with specs and requirements

Finished in 2024

Pre-production sensor status

Thick wafers: be distributed for hybridization with ASIC at IFAE and NCAP

IHEP-IME:
12 wafers, 402 sensors

Be distributed:
IFAE: 5 wafers, 164 sensors
IHEP: 7 wafers, 238 sensors

USTC-IME:
6 wafers, 167 sensors

Be distributed:
IFAE: 5 wafers, 104 sensors
IHEP: 2 wafers, 63 sensors

For IFAE: 268 sensors,
IHEP: 301 sensors

| IHEP-IME (B5-W) | Number | Status |
|--------------------|--------|---------|
| 2 | 37 | At NCAP |
| 3 | 32 | At IFAE |
| 4 | 30 | IHEP |
| 5 | 34 | IFAE |
| 6 | 38 | IFAE |
| 7 | 27 | IHEP |
| 9 | 22 | IFAE |
| 14 | 38 | IFAE |
| 15 | 35 | IHEP |
| 18 | 41 | IHEP |
| 22 | 36 | IHEP |
| 24 | 32 | IHEP |

| USTC-IME | Number | Status |
|----------|--------|---------|
| 16 | 23 | At IFAE |
| 17 | 34 | IHEP |
| 18 | 29 | IHEP |
| 19 | 30 | IFAE |
| 20 | 25 | IFAE |
| 21 | 26 | IFAE |
| 22 | 25 | At USTC |





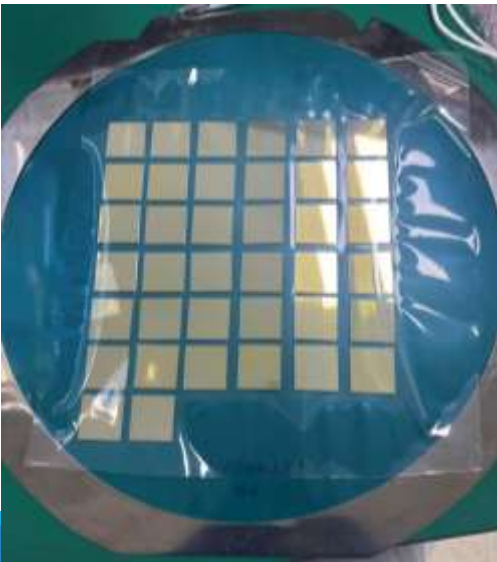
Production status: pilot batch

- **IHEP-IME Pilot batch** been delivered to IHEP on 15th May, including main sensors and QC-TS.
- **17 wafers: 403 good sensors** and 17x25 QC-TS.
- Sensor quality check be done by IHEP. 17x25 QC-TS will be distributed to CERN, USP and JSI for process quality check and irradiation test.

Table 1: Number of good sensors for wafers [from B4-W2 to B4-W19]

| Wafer serial number | W2 | W3 | W4 | W5 | W6 | W8 |
|------------------------|-----|-----|-----|-----|-----|-------|
| Number of good sensors | 20 | 12 | 25 | 22 | 26 | 35 |
| Wafer serial number | W9 | W10 | W11 | W12 | W13 | W14 |
| Number of good sensors | 27 | 26 | 27 | 29 | 22 | 29 |
| Wafer serial number | W15 | W16 | W17 | W18 | W19 | Total |
| Number of good sensors | 26 | 15 | 16 | 24 | 22 | 403 |

Yield: $403/884 = \sim 45\%$



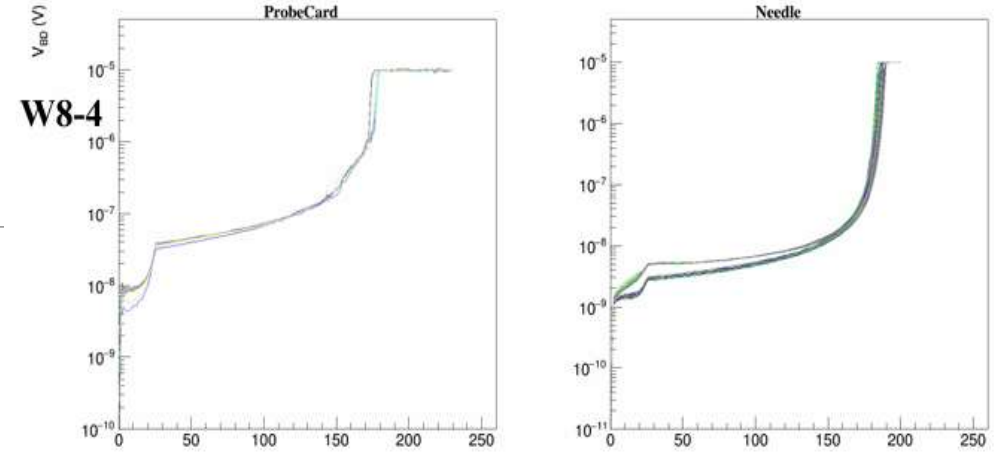
Pilot batch: SQC

SQC: sensors quality check, done by IHEP

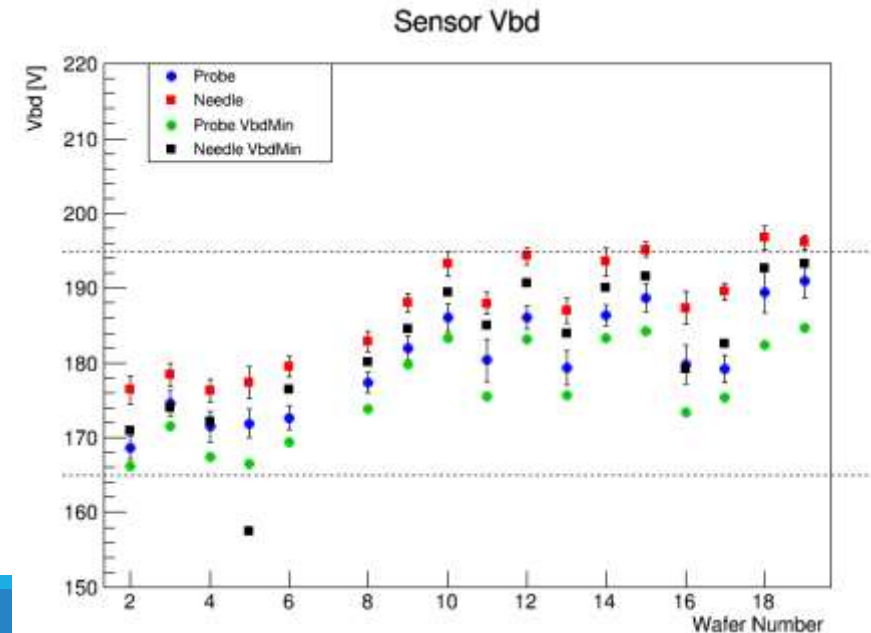
1、Used probe station to measure the I-V curve of each channel 【per-pad needle test】

Calculate the sensor information: V_{bd} , V_{bd} spread, I_{ratio}

2、**20 Class-A** been tested and results compared with IME's
19 remain A; 1 (W5P7) → B1($V_{bd} < 165V$);



3、 V_{bd} from the needle test(IHEP) was 2~10 V higher than the probe card test(IME);



| Wafer Serial Number (B4) | Sensor Number | Probe Card | | | Needle | | | | |
|-----------------------------|------------------|-----------------|----------------------------------|---------|-----------------|----------------------------------|---------|-----------|-------|
| | | V_{bd} Min[V] | RMS/ $\langle V_{bd} \rangle$ | I ratio | V_{bd} Min[V] | RMS/ $\langle V_{bd} \rangle$ | I ratio | I ratio-o | Class |
| W2 | 5 | 166.22 | 0.90% | 1.07 | 170.97 | 1.08% | 3.43 | 1.49 | A |
| W4 | 5 | 167.34 | 1.20% | 1.10 | 172.17 | 0.89% | 3.72 | 1.41 | A |
| W5 | 7 | 166.54 | 1.12% | 1.16 | 157.52 | 1.20% | 3.59 | 1.35 | B1 |
| W6 | 6 | 169.45 | 0.95% | 1.09 | 176.46 | 0.78% | 3.44 | 1.32 | A |
| W13 | 3 | 175.74 | 1.25% | 1.24 | 183.98 | 0.89% | 3.51 | 1.42 | A |
| W16 | 5 | 173.43 | 1.42% | 1.50 | 179.25 | 1.19% | 3.75 | 1.44 | A |
| W19 | 8 | 184.77 | 1.15% | 2.58 | 193.24 | 0.48% | 4.23 | 1.35 | A |
| W3 | 28 | 171.60 | 0.98% | 2.11 | 174.01 | 0.82% | 3.28 | 1.32 | A |
| W8 | 4 | 173.84 | 0.77% | 1.20 | 180.05 | 0.77% | 3.09 | 1.34 | A |
| W9 | 6 | 179.74 | 0.89% | 1.90 | 184.53 | 0.62% | 3.37 | 1.28 | A |
| W10 | 6 | 183.31 | 0.95% | 1.91 | 189.46 | 0.87% | 3.66 | 1.38 | A |
| W11 | 6 | 175.47 | 1.57% | 1.29 | 184.97 | 0.74% | 3.34 | 1.36 | A |
| W12 | 6 | 183.19 | 0.83% | 2.38 | 190.66 | 0.56% | 3.90 | 1.31 | A |
| W14 | 4 | 183.29 | 0.76% | 1.70 | 190.03 | 0.99% | 3.33 | 1.39 | A |
| W15 | 6 | 184.25 | 1.01% | 2.41 | 191.62 | 0.53% | 3.49 | 1.29 | A |
| W17 | 6 | 175.30 | 1.04% | 1.59 | 182.52 | 0.60% | 3.36 | 1.28 | A |
| W18 | 3 | 182.47 | 1.45% | 3.15 | 192.62 | 0.80% | 4.17 | 1.37 | A |

Pilot batch: process quality check



➤ 17 wafers of IHEP-IME Pilot batch

- 10 QC-TS/wafer tested by CERN and 10 QC-TS/wafer at CERN USP
- Wafer acceptance criteria on spread of gain-layer depletion voltage:

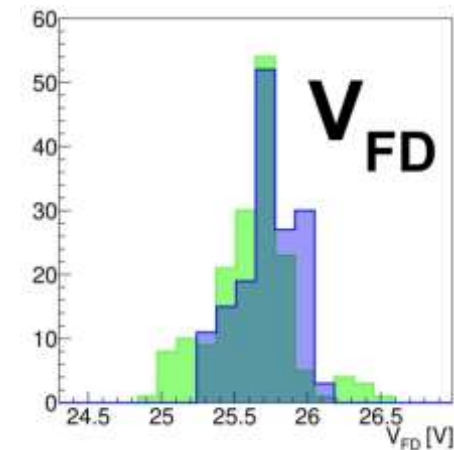
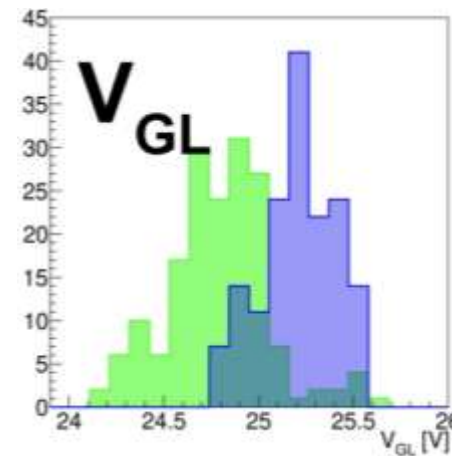
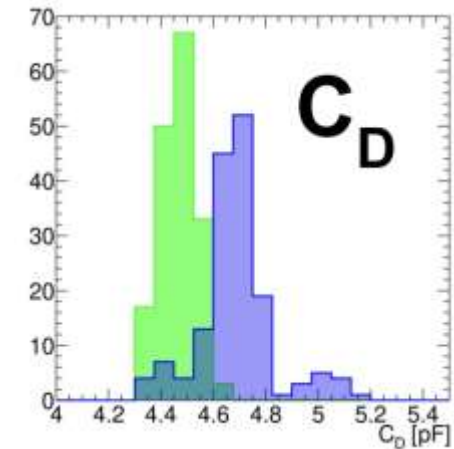
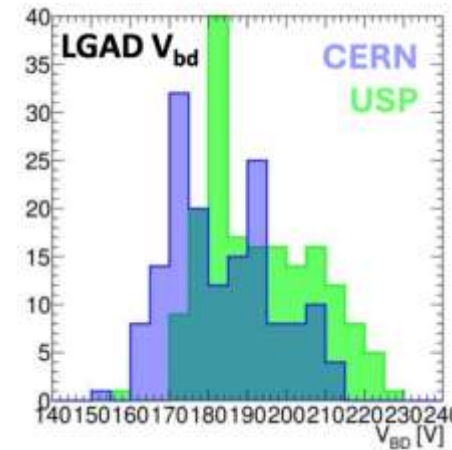
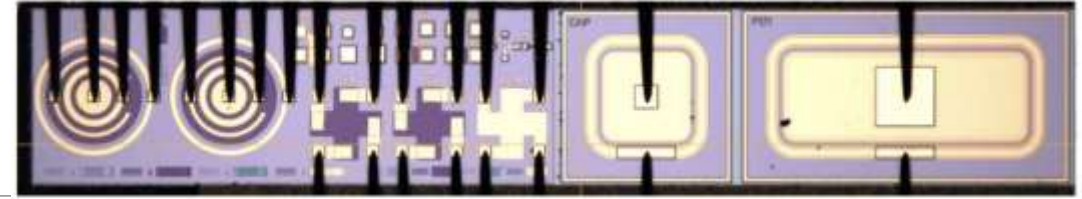
$$\text{Spread} = \frac{\text{RMS}(V_{gl})}{\text{AVERAGE}(V_{gl})} < 2\%$$

- LGAD IV and CV: Results for sites individually ok, slight discrepancy between USP and CERN in V_{gl} and C_D

V_{gl} spread

- ✓ USP 17/17 wafer would **pass** PQC
- ✓ CERN 17/17 wafer would **pass** PQC

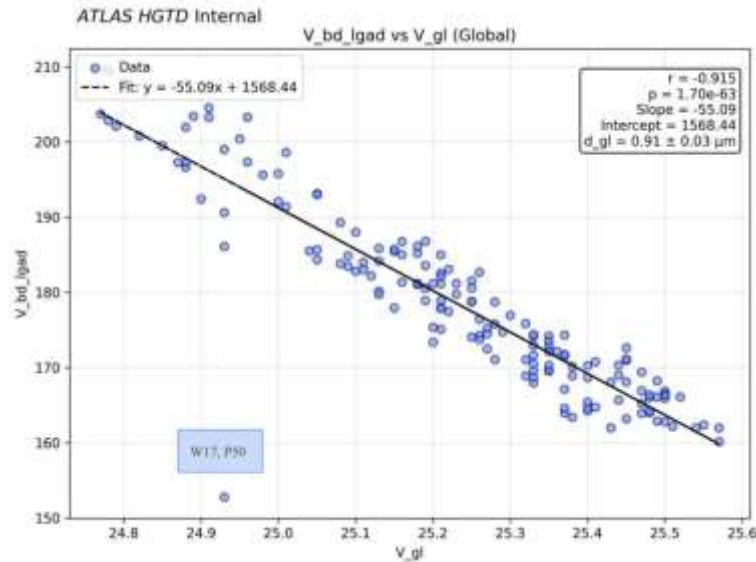
C_D : average of 4.45 pF



Pilot batch: process quality check

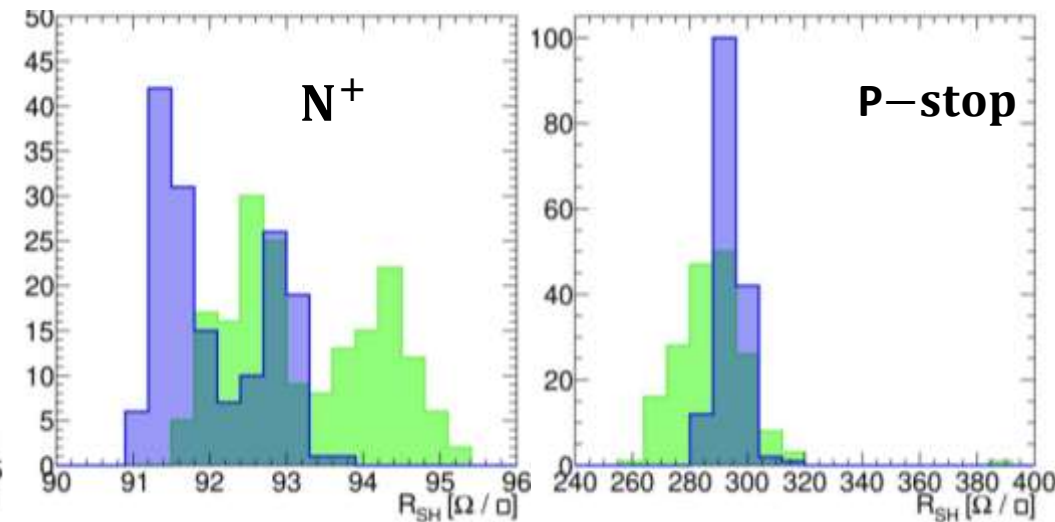
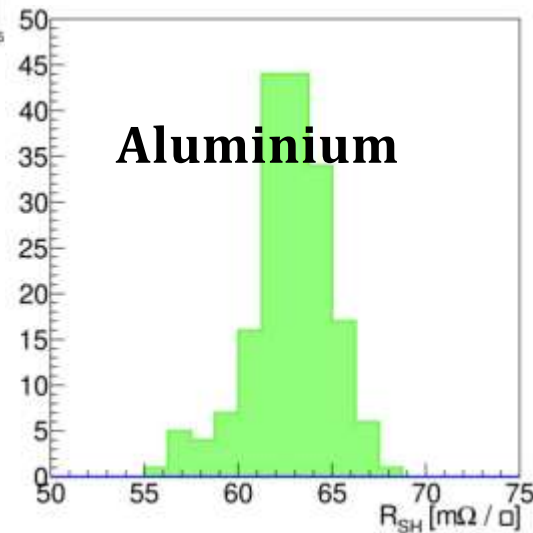
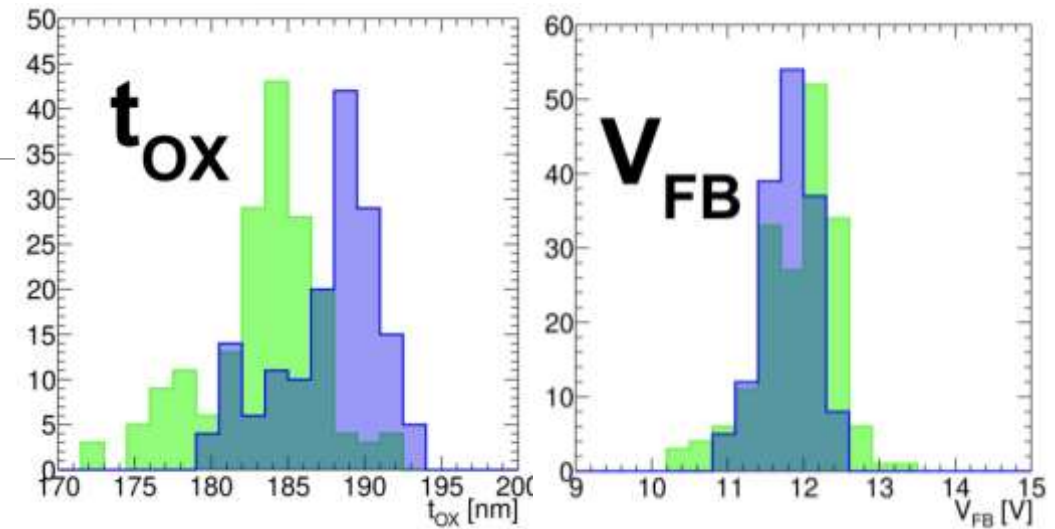


➤ V_{gl} vs. V_{bd} : strong correlation observed as expected



➤ Other process parameters: V_{FB} , Oxide thickness, N^+ , p-stop and Aluminium sheet resistance:

- Very low spread, indicating uniform process parameters
- Good agreement between sites
- with same spread as pre-production



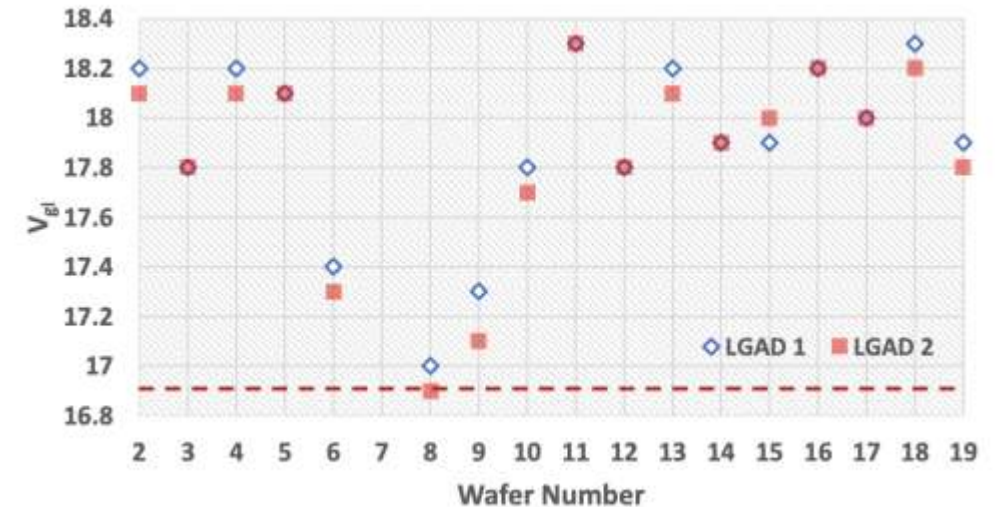
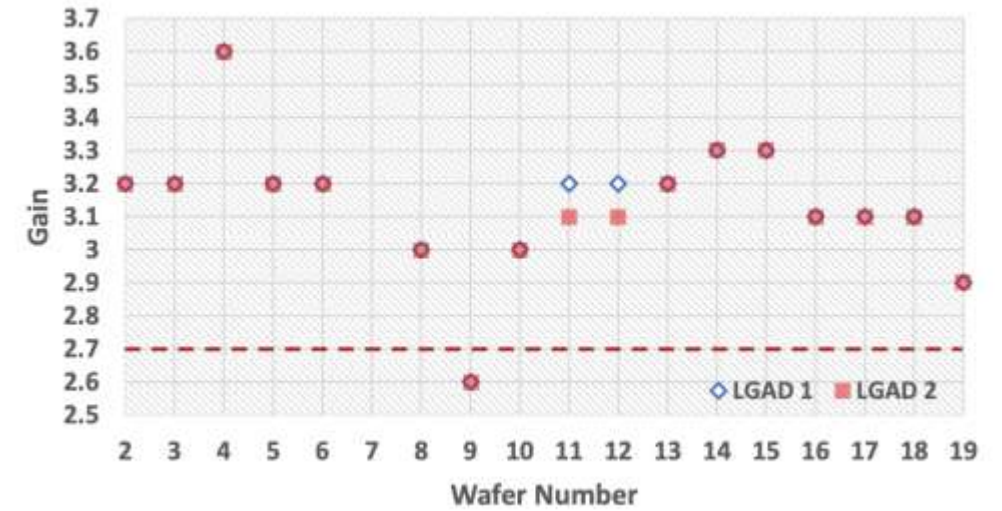
Pilot batch: Irradiation Test



- Irradiation Test: QC-TS are irradiated at JSI with neutrons at end-of-life fluence($2.5 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$) (annealed for 80min at 60°C)
- 5 QCTS/wafer at JSI, 1 QC-TS/wafer tested by JSI
- Transient Current Technique (TCT) measurement:
 - Gain @ 100V measured with the TCT method in the inter-pad region of the 1x2 LGAD of the QC-TS
 - Inter-pad region: no gain layer → PIN diode
- CV measurement: V_{gl}
- Acceptance Criteria:

| Design | Gain @ 100 V | V_{gl} |
|--------|--------------|---------------------|
| IHEP | ≥ 2.7 | $\geq 16.9\text{V}$ |
| USTC | ≥ 1.4 | $\geq 16.6\text{V}$ |

- ❑ All wafers pass V_{gl} requirements
- ❑ One wafer (9) barely fails gain criteria(to do Sr90 measurements on W9)



Issues: in-kind Contract

In-kind contract:

24% IHEP: 5232 sensors, 10% USTC: 2180 sensors

- 1、 Middle of this year, IME provided the price for this part, which is too high, 10 times of CERN price.
- 2、 The contract of this part need to be signed promptly, as it is subject to the funding timeline.

Solution:

- B1 sensors been tested to check if these sensors also can be used. In fact these sensors with lower BV at beginning have good radiation performance.
- Together with A type sensors, many B1 sensors been fabricated.

B1 sensors may be accepted for in-kind sensors.

Pilot batch [884 sensors]
Class A 371.00 [42%]
Class B1 131.00 [14.8%]
Class B2 101.00

For CERN: total 11723 A sensors
Follow this yield, then more than 4000
B1 sensors will be fabricated.

In fact, 6 batches(150 wafers) are all
B1 wafers

Acceptance of B1 sensors

Test of B1 sensors:

Main sensor + Hybrid test

**Total: 19 B1 tested, 12 good B1(actually A type).
63% yield.**

| | | CQC: Probe card | | | SQC: Needle, per-pad | | | class |
|-----------|-------|-----------------|----------------|-------------|----------------------|------------------------|-------------|-------|
| | | $V_{bd}Min(V)$ | $RMS/<V_{bd}>$ | I_{ratio} | $V_{bd}Min(V)$ | $RMS/<V_{bd}>$ | I_{ratio} | |
| IHEP test | B1 | | | | | | | |
| | w3-8 | 163.36 | 0.72% | 1.23 | 174.08 | 3.62 | 1.31 | A |
| | w3-18 | 154.63 | 1.09% | 1.1 | 167.67 | 3.51 | 1.30 | A |
| JSI test | w5-5 | 163.9 | 1.49% | 1.17 | 13.5(171) | | | C |
| | w5-8 | 162.8 | 1.36% | 1.09 | | Be damaged during test | | |
| | w5-17 | 153.7 | 1.89% | 1.15 | 136.7(169) | | | C |
| | w5-20 | 155.8 | 1.50% | 1.33 | 167.2 | | | A |
| | w5-35 | 153.4 | 1.59% | 1.37 | 161.9 | | | B2 |

One bad pixel: near GR

One bad pixel: near GR

| type | Hybrid number | good | issue |
|------|---------------|--------|---|
| B1 | 13 | 9(69%) | 1 with large leakage current(w6-18) 3 with current steps [w5-44,w5-50,w6-49] |

IT test of B1 sensors(JSI):

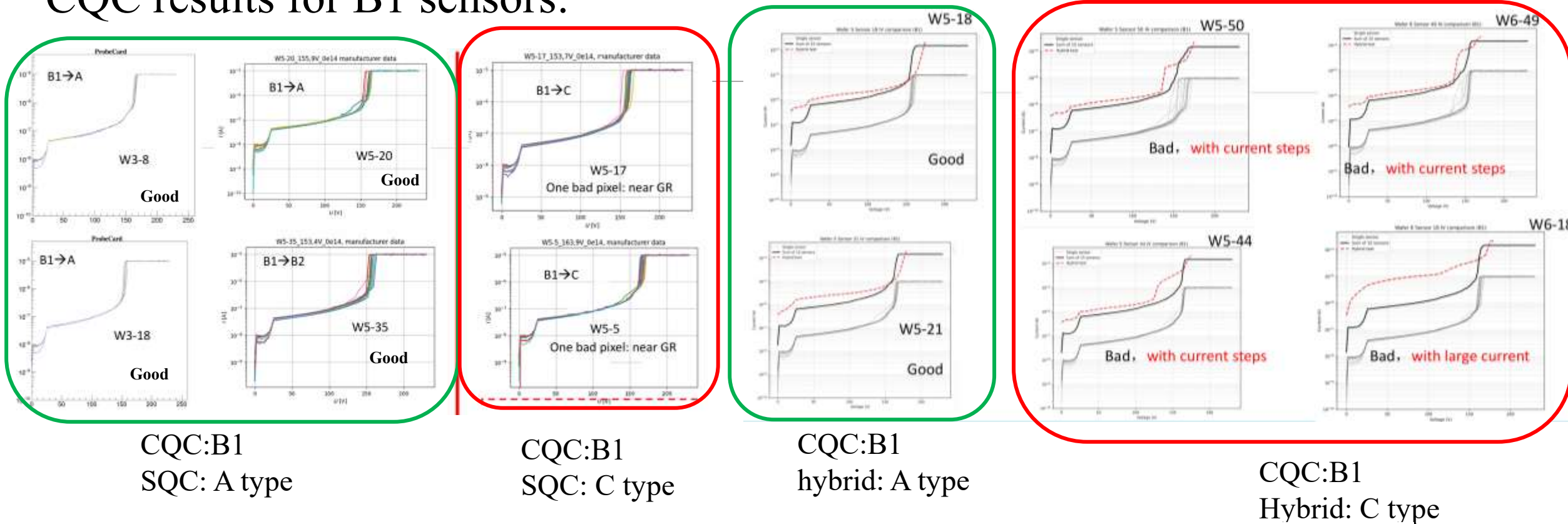
| | CQC | SQC | SQC 4e14 | Vbd CQC | Vbd SQC Average $V_{bd}(V_{bd,min})$ | Mean $V@95uA [V]$ | ΔV_{app} [V] | RMS $V@95uA$ | $<I>@0.8^*$ $V95uA$ | $RMS<I>@0.8^*V95uA$ |
|--------|----------|---------|--------------|---------|---|----------------------|-------------------------|-----------------|------------------------|---------------------|
| W3-27 | Class A | Class A | "Class A IV" | 169.3 | 170.5 | 221.8 | ~51 | 0.79 | 34.8 | 0.35 |
| W10-5 | Class A | Class A | "Class A IV" | 175.7 | 182.8 | 233.6 | ~52 | 2.1 | 33.8 | 0.92 |
| W5-5 | Class B1 | Class C | "Class A IV" | 163.9 | 172.0 (25*) | 224.2 | ~52 | 2.1 | 35.3 | 0.92 |
| W5-17 | Class B1 | Class C | "Class A IV" | 153.7 | 172.2 (137*) | 218.1 | ~48 | 1.7 | 35 | 0.73 |
| W19-47 | Class B2 | Class C | "Class A IV" | 182.2 | 203 (90*) | 250.4 | ~47 | 1.74 | 32.6 | 0.8 |
| W19-49 | Class B2 | Class C | "Class A IV" | 179.7 | 204 (145*) | 246.5 | ~42 | 2.2 | 33.8 | 0.94 |

After moderate irradiation the detectors of all three classes[A, B1, B2] have similar performance, all are suitable for use!

Beam test, Stefano(CERN): first glance of the hybrids look fine (with A sensors, B1 and B2 sensor).

Acceptance of B1 sensors

CQC results for B1 sensors:



- Good B1 has lower V_{bd} spread.
 V_{bd} Spread for A is 5%, for B1, $RMS(V_{bd})/\langle V_{bd} \rangle < 1.5\%$?
- More statistics are needed to get conclusion of Acceptance criteria for B1 sensors.
- 50 B1 sensors hybrid will be done, 30 B1 sensors plan to be tested in this month.

LGAD sensor status-summary

➤Contract

IME and CERN contract be signed at beginning of 2025.

➤Pre-production

LGAD sensors' pre-production is finished in 2024, and IHEP-IME(19 wafers) and USTC-IME(5 wafers) sensors fulfill the project requirement.

Sensors from 12 IHEP-IME and 6 USTC-IME thick wafers being used for hybridization now.

➤Production

Pilot batch is finished; sensors be distributed to IHEP in May 2025. Quality test done, results show the A type sensors pass the requirement. [SQC,PQC, IT]

➤Next batches for CERN part will be finished before August 2026.

➤In-kind contract need to be signed soon, B1 sensors may be accepted as in-kind part sensors. More cross check test need to be done on B1 sensors and decide the Acceptance criteria .